

METHOD AND APPARATUS TO CORRECT WAFER DRIFT

Abstract of the Disclosure

A method and apparatus is provided for determining workpiece drift from its nominal or intended position. The apparatus includes two proportionate sensors, each of which gives an output reading that depends upon how much of the sensor beam is blocked by an edge of the workpiece. A computer can calculate positional drift based upon these readings. Also disclosed is a method for aligning proportionate sensors to be parallel to one another.

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